



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Daniel MEISEL et al.

U.S. Application No.: 10/522,162

Filing Date: September 27, 2005

For: METHOD FOR THE PRODUCTION
OF PHOTORESIST STRUCTURES

Art Unit: 1752

Examiner: Amanda C. Walke

Confirmation No.: 9144

Atty. Docket No.: 31775-210910

Customer No.: **26694**

Amendment

MS Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

In response to the Office Action dated October 3, 2007, please amend the above-identified U.S. patent application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 5 of this paper.